Tatsuru Shirafuji

List of Publications by Year
in descending order

39	377	933447 10	794594 19
papers	citations	h-index	g-index

39	39	39	281
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Total reflection X-ray fluorescence analysis with a glass substrate treated with a He atmospheric pressure plasma jet. Journal of Analytical Atomic Spectrometry, 2021, 36, 1873-1878.	3.0	7
2	Rapid Measurement of Yeast Status using the Phase Angles of Harmonics in the Electrical Response Waveform. IEEJ Transactions on Fundamentals and Materials, 2021, 141, 239-244.	0.2	2
3	In vivo study on the healing of bone defect treated with non-thermal atmospheric pressure gas discharge plasma. PLoS ONE, 2021, 16, e0255861.	2.5	8
4	Recent Progress in Electrical Discharges, Plasma, and Pulsed Power Technologies. IEEJ Transactions on Fundamentals and Materials, 2020, 140, 10-11.	0.2	0
5	Rethinking surface reactions in nanoscale dry processes toward atomic precision and beyond: a physics and chemistry perspective. Japanese Journal of Applied Physics, 2019, 58, SE0801.	1.5	9
6	Tailoring the Chemistry of Plasma-Activated Water Using a DC-Pulse-Driven Non-Thermal Atmospheric-Pressure Helium Plasma Jet. Plasma, 2019, 2, 127-137.	1.8	13
7	Reaction Kinetics of Active Species from an Atmospheric Pressure Plasma Jet Irradiated on the Flowing Water Surface â€" Effect of Gas-drag by the Sliding Water Surface â€". Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2019, 32, 535-540.	0.3	0
8	Recent Progress in Plasma and Pulsed Power Technologies. IEEJ Transactions on Fundamentals and Materials, 2019, 139, 9-10.	0.2	0
9	The Dependence of Nonlinear Electrical Properties of Yeast Suspensions on Temperature and Electrode Shape. IEEJ Transactions on Fundamentals and Materials, 2019, 139, 339-344.	0.2	1
10	The Japan Society of Vacuum and Surface Science Accepts Plasmas in Atmospheric Pressure and in Liquid. Vacuum and Surface Science, 2019, 62, 543-543.	0.1	0
11	Autumn Joint Lecture of Kansai Branches. Vacuum and Surface Science, 2019, 62, 735-735.	0.1	0
12	æ¶²ä½“ä¸Žã•ã‚Œé–¢ä¸Žã™ã‚‹ãƒ—ãƒ©ã‚ºãƒžæ–™ãƒ—ãƒã‚»ã‚·ãƒ³ã‚°. Vacuum and Surface Science, 2018, 61, 119-130.	0.1	1
13	Recent Progress in Plasma Technology. IEEJ Transactions on Fundamentals and Materials, 2018, 138, 8-9.	0.2	0
14	Recognition of Single Japanese Sounds using sEMG Signals and Membership Functions. IEEJ Transactions on Electronics, Information and Systems, 2016, 136, 1821-1826.	0.2	3
15	Three-Dimensionally Integrated Micro-solution Plasma: Numerical Feasibility Study and Practical Applications. Plasma Chemistry and Plasma Processing, 2014, 34, 523-534.	2.4	8
16	Plasmas in Contact with Liquid: ^|^ldquo;Plasma Electrochemistry^|^rdquo;. Hyomen Kagaku, 2013, 34, 547-552.	0.0	2
17	Generation of Three-Dimensionally Integrated Micro Solution Plasmas and Its Application to Decomposition of Organic Contaminants in Water. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2013, 26, 507-511.	0.3	15
18	Numerical Investigation of Electric Field in Gas Bubbles Surrounded with Conductive Liquid and Dielectric Material. Transactions of the Materials Research Society of Japan, 2013, 38, 321-323.	0.2	9

#	Article	IF	Citations
19	Chemical Reaction Engineering of Plasma CVD. Journal of High Temperature Society, 2011, 37, 281-288.	0.1	1
20	Generation of Plasmas in Multiphase Medium. Transactions of the Materials Research Society of Japan, 2010, 35, 81-83.	0.2	9
21	Semianalytical Finite Element Method Model for Radio Frequency Sheaths in Single- and Dual-Frequency Capacitively Coupled Plasmas. Japanese Journal of Applied Physics, 2009, 48, 090209.	1.5	6
22	Solution Plasma Surface Modification for Nanocarbon-Composite Materials. Nippon Kinzoku Gakkaishi/Journal of the Japan Institute of Metals, 2009, 73, 938-942.	0.4	16
23	Underwater microdischarge in arranged microbubbles produced by electrolysis in electrolyte solution using fabric-type electrode. Applied Physics Letters, 2008, 93, .	3.3	36
24	Plasma Copolymerization of C6F6/C5F8for Application of Low-Dielectric-Constant Fluorinated Amorphous Carbon Films and Its Gas-Phase Diagnostics UsingIn SituFourier Transform Infrared Spectroscopy. Japanese Journal of Applied Physics, 2004, 43, 2697-2703.	1.5	13
25	Observation of self-organized filaments in a dielectric barrier discharge of Ar gas. Applied Physics Letters, 2003, 83, 2309-2311.	3.3	107
26	Plasma Enhanced Chemical Vapor Deposition of Fluorinated Amorphous Carbon Films on the Surface with Reverse Tapered Microstructures. Japanese Journal of Applied Physics, 2003, 42, 4504-4509.	1.5	4
27	Dry Etching of SiO2Thin Films with Perfluoropropenoxideâ€“O2and Perfluoropropeneâ€“O2Plasmas. Japanese Journal of Applied Physics, 2002, 41, 6287-6290.	1.5	10
28	Title is missing!. Shinku/Journal of the Vacuum Society of Japan, 2000, 43, 504-511.	0.2	0
29	Plasma Copolymerization of Tetrafluoroethylene/Hexamethyldisiloxane andIn SituFourier Transform Infrared Spectroscopy of Its Gas Phase. Japanese Journal of Applied Physics, 1999, 38, 4520-4526.	1.5	39
30	Plasma Enhanced Chemical Vapor Deposition of Fluorinated Amorphous Carbon Thin Films from Tetrafluoroethylene and Tetraisocyanatesilane. Plasmas and Polymers, 1998, 3, 115-127.	1.5	5
31	Preparation of Stable F-Doped SiO2Thin Films from Si(NCO)4/SiF4/O2Gas Mixtures Using a Conventional Capacitively Coupled RF Plasma Source. Japanese Journal of Applied Physics, 1997, 36, 4911-4916.	1.5	4
32	Diamond Nucleation on Singlecrystalline 6H-SiC Substrates by Bias-Enhanced Nucleation in Hot Filament Chemical Vapor Deposition. Japanese Journal of Applied Physics, 1997, 36, 6295-6299.	1.5	9
33	Construction and Performance of a Fourier-Transform Infrared Phase-Modulated Ellipsometer for In-Process Surface Diagnostics. Japanese Journal of Applied Physics, 1996, 35, 3652-3657.	1.5	6
34	Thickness Dependence of H Radical Treatment of Si Thin Films Deposited by Plasma-Enhanced Chemical Vapor Deposition Using SiF4/SiH4/H2Gases. Japanese Journal of Applied Physics, 1996, 35, 2047-2051.	1.5	1
35	Measurement and Calculation of $f SiH_{2}$ Radical Density in $f SiH_{4}$ and $f Si_{2}H_{6}$ Plasma for the Deposition of Hydrogenated Amorphous Silicon Thin Films. Japanese Journal of Applied Physics, 1995, 34, 4239-4246.	1.5	17
36	In Situ Ellipsometric Monitoring of the Growth of Polycrystalline Silicon Thin Films by RF Plasma Chemical Vapor Deposition. Japanese Journal of Applied Physics, 1994, 33, 4191-4194.	1.5	13

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37	Low-Temperature Growth Process of Polycrystalline Silicon for Thin Film Transistors.. Shinku/Journal of the Vacuum Society of Japan, 1994, 37, 875-880.	0.2	1
38	A-Si:H Deposited by Direct Photo-Cvd Using a Microwave-Excited Xe Lamp. Materials Research Society Symposia Proceedings, 1990, 192, 505.	0.1	1
39	Enhanced decomposition of toxic pollutants by underwater pulsed discharge in the presence of hydrogen peroxide and microbubbles. Japanese Journal of Applied Physics, 0, , .	1.5	1